

	Hit s	Search Text	DBs
29	27	((mask or photomask or reticle or (pattern\$4 near5 (device or structure))) same (substrate or wafer or workpiece)) and ((mask or (pattern\$4 near5 (device or structure)) or reticle) same (absorb\$4 or aluminum or Al) same ((protective or top\$3coat\$4 or (top near4 layer) or (aluminum near9 oxide)) near26 (\$2nm or thickness\$3 or thick)) same (buffer near5 layer))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
30	2	S34 NOT S33	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
31	29	((mask or photomask or reticle or (pattern\$4 near5 (device or structure))) same (substrate or wafer or workpiece)) and ((mask or (pattern\$4 near5 (device or structure)) or reticle or photomask) same (absorb\$4 or aluminum or Al) same ((protective or top\$3coat\$4 or (top near4 layer) or (aluminum near9 oxide)) near26 (\$2nm or thickness\$3 or thick)) same (buffer near6 (coat\$3 or film or deposit\$3 or layer)))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
32	0	S36 NOT S34	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB

	Hit s	Search Text	DBs
33	10	\$4lithograph\$5 and ((mask or photomask or reticle or (pattern\$4 near5 (device or structure))) same (substrate or wafer or workpiece)) and ((mask or (pattern\$4 near5 (device or structure)) or reticle) same (absorb\$4 or aluminum or Al) same ((protective or top\$3coat\$4 or (top near4 layer) or (aluminum near9 oxide)) near26 (\$2nm or thickness\$3 or thick)) same (buffer near5 layer))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
34	4	((mask or photomask or reticle or (pattern\$4 near5 (device or structure))) near4 (EUV or (EUV near4 reflective))) and ((photomask or mask or (pattern\$4 near5 (device or structure)) or reticle) same (absorb\$4 or aluminum or Al)) and ((mask or reticle or photomask) same ((multi\$4layer near12 reflective) or (multi\$4layer near5 mirror)) same high same low same index same (material or layer)) and (absorb\$4 same (protective or top\$3coat\$4 or (top near4 layer) or (aluminum near9 oxide)) same (thickness\$3 or thick) same (nanometer or nm))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB

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35	31	((mask or photomask or reticle or (pattern\$4 near5 (device or structure))) near4 (EUV or (EUV near4 reflective))) and ((photomask or mask or (pattern\$4 near5 (device or structure)) or reticle) same (absorb\$4 or aluminum or Al)) and ((mask or reticle or photomask) same ((multi\$4layer near12 reflective) or (multi\$4layer near5 mirror))) and (absorb\$4 same (protective or top\$3coat\$4 or (top near4 layer) or (aluminum near9 oxide))) same (thickness\$3 or thick) same (nanometer or nm))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB